

Anjana Devi

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h-index

51
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227
ext. papers

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ext. citations

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avg, IF

5.24
L-index

#	Paper	IF	Citations
209	1D ZnO nano-assemblies by Plasma-CVD as chemical sensors for flammable and toxic gases. <i>Sensors and Actuators B: Chemical</i> , 2010 , 149, 1-7	8.5	150
208	F-Doped Co ₃ O ₄ photocatalysts for sustainable H ₂ generation from water/ethanol. <i>Journal of the American Chemical Society</i> , 2011 , 133, 19362-5	16.4	149
207	Co ₃ O ₄ /ZnO nanocomposites: from plasma synthesis to gas sensing applications. <i>ACS Applied Materials & Interfaces</i> , 2012 , 4, 928-34	9.5	125
206	Old Chemistries for new applications: Perspectives for development of precursors for MOCVD and ALD applications. <i>Coordination Chemistry Reviews</i> , 2013 , 257, 3332-3384	23.2	106
205	Highly Oriented ZnO Nanorod Arrays by a Novel Plasma Chemical Vapor Deposition Process. <i>Crystal Growth and Design</i> , 2010 , 10, 2011-2018	3.5	85
204	Urchin-like ZnO nanorod arrays for gas sensing applications. <i>CrystEngComm</i> , 2010 , 12, 3419	3.3	82
203	Plasma-assisted synthesis of Ag/ZnO nanocomposites: First example of photo-induced H ₂ production and sensing. <i>International Journal of Hydrogen Energy</i> , 2011 , 36, 15527-15537	6.7	71
202	Hafnium oxide thin film grown by ALD: An XPS study. <i>Surface Science Spectra</i> , 2007 , 14, 34-40	1.2	68
201	Growth and Crystallization of TiO ₂ Thin Films by Atomic Layer Deposition Using a Novel Amido Guanidinate Titanium Source and Tetrakis-dimethylamido-titanium. <i>Chemistry of Materials</i> , 2013 , 25, 2934-2943	9.6	65
200	Fabrication of heterostructured p-CuO/n-SnO ₂ core-shell nanowires for enhanced sensitive and selective formaldehyde detection. <i>Sensors and Actuators B: Chemical</i> , 2019 , 290, 233-241	8.5	64
199	A Study of Bisazido(dimethylamino-propyl)gallium as a Precursor for the OMVPE of Gallium Nitride Thin Films in a Cold-Wall Reactor System under Reduced Pressure. <i>Chemical Vapor Deposition</i> , 2000 , 6, 245-252		63
198	Fe ₂ O ₃ nanomaterials from an iron(II) diketonate-diamine complex: a study from molecular precursor to growth process. <i>Dalton Transactions</i> , 2012 , 41, 149-55	4.3	57
197	A Study on the Metal Organic CVD of Pure Copper Films from Low Cost Copper(II) Dialkylamino-2-propoxides: Tuning the Thermal Properties of the Precursor by Small Variations of the Ligand. <i>Chemical Vapor Deposition</i> , 2003 , 9, 149-156		57
196	Review Article: Recommended reading list of early publications on atomic layer deposition Outcome of the Virtual Project on the History of ALD. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 010801	2.9	55
195	CuO/ZnO nanocomposite gas sensors developed by a plasma-assisted route. <i>ChemPhysChem</i> , 2012 , 13, 2342-8	3.2	51
194	Plasma enhanced-CVD of undoped and fluorine-doped Co ₃ O ₄ nanosystems for novel gas sensors. <i>Sensors and Actuators B: Chemical</i> , 2011 , 160, 79-86	8.5	50
193	Synthesis, characterization, and thermal properties of homoleptic rare-earth guanidinate: promising precursors for MOCVD and ALD of rare-earth oxide thin films. <i>Inorganic Chemistry</i> , 2008 , 47, 11405-16	5.1	50

192	Strongly oriented thin films of Co ₃ O ₄ deposited on single-crystal MgO(1 0 0) by low-pressure, low-temperature MOCVD. <i>Journal of Crystal Growth</i> , 2002 , 240, 157-163	1.6	49
191	Guanidinate-stabilized monomeric hafnium amide complexes as promising precursors for MOCVD of HfO ₂ . <i>Inorganic Chemistry</i> , 2006 , 45, 11008-18	5.1	47
190	Investigations on InN whiskers grown by chemical vapour deposition. <i>Journal of Crystal Growth</i> , 2001 , 231, 68-74	1.6	47
189	Synthesis of nano-scale TiO ₂ particles by a nonhydrolytic approach. <i>Journal of Materials Chemistry</i> , 2002 , 12, 1625-1627		45
188	Homoleptic gadolinium guanidinate: a single source precursor for metal-organic chemical vapor deposition of gadolinium nitride thin films. <i>Journal of the American Chemical Society</i> , 2009 , 131, 17062-3	16.4	44
187	Ag/ZnO nanomaterials as high performance sensors for flammable and toxic gases. <i>Nanotechnology</i> , 2012 , 23, 025502	3.4	42
186	Growth of crystalline Gd ₂ O ₃ thin films with a high-quality interface on Si(100) by low-temperature H ₂ O-assisted atomic layer deposition. <i>Journal of the American Chemical Society</i> , 2010 , 132, 36-7	16.4	40
185	An integrated experimental and theoretical investigation on Cu(hfa) ₂ . TMEDA: structure, bonding and reactivity. <i>Physical Chemistry Chemical Physics</i> , 2009 , 11, 5998-6007	3.6	40
184	Atomic Layer Deposition of Gd ₂ O ₃ and Dy ₂ O ₃ : A Study of the ALD Characteristics and Structural and Electrical Properties. <i>Chemistry of Materials</i> , 2012 , 24, 651-658	9.6	38
183	A cobalt(II) hexafluoroacetylacetonate ethylenediamine complex as a CVD molecular source of cobalt oxide nanostructures. <i>Inorganic Chemistry</i> , 2009 , 48, 82-9	5.1	38
182	Lanthanide Oxide Thin Films by Metalorganic Chemical Vapor Deposition Employing Volatile Guanidinate Precursors. <i>Chemistry of Materials</i> , 2009 , 21, 5443-5455	9.6	38
181	ZnO nanorod arrays by plasma-enhanced CVD for light-activated functional applications. <i>ChemPhysChem</i> , 2010 , 11, 2337-40	3.2	38
180	Low temperature growth of gallium oxide thin films via plasma enhanced atomic layer deposition. <i>Dalton Transactions</i> , 2017 , 46, 16551-16561	4.3	37
179	Evaluation of Homoleptic Guanidinate and Amidinate Complexes of Gadolinium and Dysprosium for MOCVD of Rare-Earth Nitride Thin Films. <i>Chemistry of Materials</i> , 2011 , 23, 1430-1440	9.6	37
178	Low Temperature Stabilization of Nanoscale Epitaxial Spinel Ferrite Thin Films by Atomic Layer Deposition. <i>Advanced Functional Materials</i> , 2014 , 24, 5368-5374	15.6	36
177	Sc ₂ O ₃ , Er ₂ O ₃ , and Y ₂ O ₃ thin films by MOCVD from volatile guanidinate class of rare-earth precursors. <i>Dalton Transactions</i> , 2012 , 41, 13936-47	4.3	35
176	Volatile, Monomeric, and Fluorine-Free Precursors for the Metal Organic Chemical Vapor Deposition of Zinc Oxide. <i>European Journal of Inorganic Chemistry</i> , 2010 , 2010, 1366-1372	2.3	35
175	Stabilization of Amide-Based Complexes of Niobium and Tantalum Using Malonates as Chelating Ligands: Precursor Chemistry and Thin Film Deposition. <i>Chemistry of Materials</i> , 2007 , 19, 6077-6087	9.6	35

174	Direct Growth of MoS ₂ and WS ₂ Layers by Metal Organic Chemical Vapor Deposition. <i>Advanced Materials Interfaces</i> , 2018 , 5, 1800140	4.6	34
173	Electrical and optical properties of TiO ₂ thin films prepared by plasma-enhanced atomic layer deposition. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2014 , 211, 416-424	1.6	34
172	Low-Temperature Atomic Layer Deposition of Cobalt Oxide as an Effective Catalyst for Photoelectrochemical Water-Splitting Devices. <i>Chemistry of Materials</i> , 2017 , 29, 5796-5805	9.6	32
171	Strain-induced phase transitions in epitaxial NaNbO ₃ thin films grown by metalorganic chemical vapour deposition. <i>Journal of Applied Crystallography</i> , 2012 , 45, 1015-1023	3.8	32
170	Intrinsic Nitrogen-doped CVD-grown TiO ₂ Thin Films from All-N-coordinated Ti Precursors for Photoelectrochemical Applications. <i>Chemical Vapor Deposition</i> , 2013 , 19, 45-52		32
169	Nanostructured Dy ₂ O ₃ films: An XPS Investigation. <i>Surface Science Spectra</i> , 2007 , 14, 52-59	1.2	32
168	Design, synthesis and antimicrobial evaluation of novel 1-benzyl 2-butyl-4-chloroimidazole embodied 4-azafluorenones via molecular hybridization approach. <i>Bioorganic and Medicinal Chemistry Letters</i> , 2012 , 22, 7475-80	2.9	31
167	Synthesis and structure of mixed isopropoxide-β-ketoester and β-ketoamide zirconium complexes: Potential precursors for MOCVD of ZrO ₂ . <i>Journal of Materials Chemistry</i> , 2003 , 13, 2177-2184		31
166	Manganese(II) Molecular Sources for Plasma-Assisted CVD of Mn Oxides and Fluorides: From Precursors to Growth Process. <i>Journal of Physical Chemistry C</i> , 2018 , 122, 1367-1375	3.8	29
165	Photoactive Zinc Ferrites Fabricated via Conventional CVD Approach. <i>ACS Sustainable Chemistry and Engineering</i> , 2017 , 5, 2917-2926	8.3	28
164	MOCVD of TiO ₂ thin films and studies on the nature of molecular mechanisms involved in the decomposition of [Ti(OPri) ₂ (tbaoc) ₂]. <i>Journal of Materials Chemistry</i> , 2004 , 14, 3231-3238		28
163	Molecular Engineering of Mn Diamine Diketonate Precursors for the Vapor Deposition of Manganese Oxide Nanostructures. <i>Chemistry - A European Journal</i> , 2017 , 23, 17954-17963	4.8	27
162	Mononuclear precursor for MOCVD of HfO ₂ thin films. <i>Chemical Communications</i> , 2004 , 1610-1	5.8	27
161	A novel Cu(II) chemical vapor deposition precursor: Synthesis, characterization, and chemical vapor deposition. <i>Journal of Materials Research</i> , 1998 , 13, 687-692	2.5	27
160	MOCVD of ZnO Films from Bis(Ketoiminato)Zn(II) Precursors: Structure, Morphology and Optical Properties. <i>Chemical Vapor Deposition</i> , 2011 , 17, 155-161		26
159	Recent Advances Using Guanidinate Ligands for Chemical Vapour Deposition (CVD) and Atomic Layer Deposition (ALD) Applications. <i>Australian Journal of Chemistry</i> , 2014 , 67, 989	1.2	25
158	Plasma processing of nanomaterials: emerging technologies for sensing and energy applications. <i>Journal of Nanoscience and Nanotechnology</i> , 2011 , 11, 8206-13	1.3	25
157	Novel insight into the alignment and structural ordering of supported ZnO nanorods. <i>Chemical Physics Letters</i> , 2010 , 500, 287-290	2.5	25

156	MOCVD of gallium nitride nanostructures using $(N_3)_2Ga\{(CH_2)_3NR_2\}$, R = Me, Et, as a single molecule precursor: morphology control and materials characterization. <i>Journal of Materials Chemistry</i> , 2003 , 13, 1438		25
155	Atomic layer deposition of functional multicomponent oxides. <i>APL Materials</i> , 2019 , 7, 110901	5.7	24
154	Fabrication of ZrO ₂ and ZrN Films by Metalorganic Chemical Vapor Deposition Employing New Zr Precursors. <i>Crystal Growth and Design</i> , 2012 , 12, 5079-5089	3.5	24
153	All-nitrogen coordinated amidinato/imido complexes of molybdenum and tungsten: syntheses and characterization. <i>Inorganic Chemistry</i> , 2010 , 49, 8487-94	5.1	24
152	Heteroleptic Guanidinate- and Amidinate-Based Complexes of Hafnium as New Precursors for MOCVD of HfO ₂ . <i>European Journal of Inorganic Chemistry</i> , 2010 , 2010, 1679-01688	2.3	24
151	Liquid-Injection MOCVD of ZrO ₂ Thin Films using Zirconium Bis(diethylamido)-bis(di-tert-butylmalonato) as a Novel Precursor. <i>Chemical Vapor Deposition</i> , 2006 , 12, 295-300		24
150	Thin Films of HfO ₂ for High-k Gate Oxide Applications from Engineered Alkoxide- and Amide-Based MOCVD Precursors. <i>Journal of the Electrochemical Society</i> , 2007 , 154, G77	3.9	24
149	Water assisted atomic layer deposition of yttrium oxide using tris('diisopropyl-2-dimethylamido-guanidinato) yttrium(iii): process development, film characterization and functional properties.. <i>RSC Advances</i> , 2018 , 8, 4987-4994	3.7	23
148	Indium-tris-guanidinate: a promising class of precursors for water assisted atomic layer deposition of In ₂ O ₃ thin films. <i>Dalton Transactions</i> , 2014 , 43, 937-40	4.3	23
147	Novel Gallium Complexes with Malonic Diester Anions as Molecular Precursors for the MOCVD of Ga ₂ O ₃ Thin Films. <i>European Journal of Inorganic Chemistry</i> , 2009 , 2009, 1110-1117	2.3	23
146	PEALD of SiO and AlO Thin Films on Polypropylene: Investigations of the Film Growth at the Interface, Stress, and Gas Barrier Properties of Dyads. <i>ACS Applied Materials & Interfaces</i> , 2018 , 10, 7422-7434	9.5	22
145	An efficient PE-ALD process for TiO ₂ thin films employing a new Ti-precursor. <i>Journal of Materials Chemistry C</i> , 2016 , 4, 1057-1065	7.1	22
144	Homoleptic gadolinium amidinates as precursors for MOCVD of oriented gadolinium nitride (GdN) thin films. <i>Inorganic Chemistry</i> , 2013 , 52, 286-96	5.1	22
143	Synthesis and characterisation of zirconium-amido guanidinato complex: a potential precursor for ZrO ₂ thin films. <i>Dalton Transactions</i> , 2007 , 1671-6	4.3	22
142	Gd ₂ O ₃ Nanostructured Thin Films Analyzed by XPS. <i>Surface Science Spectra</i> , 2007 , 14, 60-67	1.2	22
141	Mononuclear Mixed β -ketoester-alkoxide Compound of Titanium as a Promising Precursor for Low-Temperature MOCVD of TiO ₂ Thin Films. <i>Chemical Vapor Deposition</i> , 2003 , 9, 295-298		22
140	Low-Temperature Plasma-Enhanced Atomic Layer Deposition of Tin(IV) Oxide from a Functionalized Alkyl Precursor: Fabrication and Evaluation of SnO-Based Thin-Film Transistor Devices. <i>ACS Applied Materials & Interfaces</i> , 2019 , 11, 3169-3180	9.5	22
139	Strongly oriented Co ₃ O ₄ thin films on MgO(100) and MgAl ₂ O ₄ (100) substrates by PE-CVD. <i>CrystEngComm</i> , 2011 , 13, 3670	3.3	21

138	Nanostructured Fe ₂ O ₃ Processing via Water-Assisted ALD and Low-Temperature CVD from a Versatile Iron Ketoiminate Precursor. <i>Advanced Materials Interfaces</i> , 2017 , 4, 1700155	4.6	20
137	Surfactant-Induced Nonhydrolytic Synthesis of Phase-Pure ZrO ₂ Nanoparticles from Metal-Organic and Oxocluster Precursors. <i>Chemistry of Materials</i> , 2012 , 24, 4274-4282	9.6	20
136	Thin Films of ZrO ₂ for High-k Applications Employing Engineered Alkoxide- and Amide-Based MOCVD Precursors. <i>Chemical Vapor Deposition</i> , 2007 , 13, 98-104		20
135	Atomic Layer Deposition of Nickel on ZnO Nanowire Arrays for High-Performance Supercapacitors. <i>ACS Applied Materials & Interfaces</i> , 2018 , 10, 468-476	9.5	20
134	Hierarchical highly ordered SnO nanobowl branched ZnO nanowires for ultrasensitive and selective hydrogen sulfide gas sensing. <i>Microsystems and Nanoengineering</i> , 2020 , 6, 30	7.7	19
133	Transition metal nitride thin films grown by MOCVD using amidinato based complexes [M(NtBu) ₂ {(iPrN) ₂ CMe ₂ } ₂] (M = Mo, W) as precursors. <i>Surface and Coatings Technology</i> , 2013 , 230, 130-136	4.4	19
132	Malonate complexes of dysprosium: synthesis, characterization and application for LI-MOCVD of dysprosium containing thin films. <i>Dalton Transactions</i> , 2011 , 40, 62-78	4.3	19
131	New amidinate complexes of indium(iii): promising CVD precursors for transparent and conductive InO thin films. <i>Dalton Transactions</i> , 2017 , 46, 10220-10231	4.3	18
130	Low-Temperature Atomic Layer Deposition of Low-Resistivity Copper Thin Films Using Cu(dmap) ₂ and Tertiary Butyl Hydrazine. <i>Chemistry of Materials</i> , 2017 , 29, 6502-6510	9.6	18
129	Hafnium carbamates and ureates: new class of precursors for low-temperature growth of HfO ₂ thin films. <i>Chemical Communications</i> , 2009 , 1978-80	5.8	18
128	MOCVD of ZrO ₂ and HfO ₂ Thin Films from Modified Monomeric Precursors. <i>Chemical Vapor Deposition</i> , 2006 , 12, 172-180		18
127	Precursor chemistry for TiO ₂ : titanium complexes with a mixed nitrogen/oxygen ligand sphere. <i>Dalton Transactions</i> , 2006 , 3485-90	4.3	18
126	Mixed amide-halonate compound of hafnium as a novel monomeric precursor for MOCVD of HfO ₂ thin films. <i>Journal of Materials Chemistry</i> , 2006 , 16, 437-440		18
125	CVD-grown copper tungstate thin films for solar water splitting. <i>Journal of Materials Chemistry A</i> , 2018 , 6, 10206-10216	13	17
124	Investigation of niobium nitride and oxy-nitride films grown by MOCVD. <i>Surface and Coatings Technology</i> , 2009 , 204, 404-409	4.4	17
123	Monomeric malonate precursors for the MOCVD of HfO ₂ and ZrO ₂ thin films. <i>Dalton Transactions</i> , 2009 , 654-63	4.3	17
122	LI-MOCVD of HfO ₂ thin films using engineered amide based Hf precursors. <i>Surface and Coatings Technology</i> , 2007 , 201, 9109-9116	4.4	17
121	Metal-Organic CVD of Conductive and Crystalline Hafnium Nitride Films. <i>Chemical Vapor Deposition</i> , 2005 , 11, 294-297		17

120	Atomic Layer Deposition of HfO ₂ Thin Films Employing a Heteroleptic Hafnium Precursor. <i>Chemical Vapor Deposition</i> , 2012 , 18, 27-35		16
119	Atomic layer deposition of Er ₂ O ₃ thin films from Er tris-guanidinate and water: process optimization, film analysis and electrical properties. <i>Journal of Materials Chemistry C</i> , 2013 , 1, 3939	7.1	16
118	[Zr(NEtMe) ₂ (guan-NEtMe) ₂] as a Novel Atomic Layer Deposition Precursor: ZrO ₂ Film Growth and Mechanistic Studies. <i>Chemistry of Materials</i> , 2013 , 25, 3088-3095	9.6	16
117	The Synthesis of ZrO ₂ /SiO ₂ Nanocomposites by the Two-Step CVD of a Volatile Halogen-Free Zr Alkoxide in a Fluidized-Bed Reactor. <i>Chemical Vapor Deposition</i> , 2007 , 13, 37-41		16
116	Atomic Layer Deposition of Molybdenum and Tungsten Oxide Thin Films Using Heteroleptic Imido-Amidinato Precursors: Process Development, Film Characterization, and Gas Sensing Properties. <i>Chemistry of Materials</i> , 2018 , 30, 8690-8701	9.6	16
115	Synthesis and evaluation of new copper ketoiminate precursors for a facile and additive-free solution-based approach to nanoscale copper oxide thin films. <i>Dalton Transactions</i> , 2017 , 46, 2670-2679	4.3	15
114	Synthesis of rare-earth metal and rare-earth metal-fluoride nanoparticles in ionic liquids and propylene carbonate. <i>Beilstein Journal of Nanotechnology</i> , 2018 , 9, 1881-1894	3	14
113	Metalorganic chemical vapor deposition of Cu films from bis(t-butyl-3-oxo-butanoato)copper(II): thermodynamic investigation and experimental verification. <i>Surface and Coatings Technology</i> , 2002 , 150, 205-211	4.4	14
112	Atomic/molecular layer deposition of hybrid inorganic/organic thin films from erbium guanidinate precursor. <i>Journal of Materials Science</i> , 2017 , 52, 6216-6224	4.3	13
111	Materials Chemistry of Group 13 Nitrides		13
110	Precursor chemistry of Group III nitrides. <i>Journal of Organometallic Chemistry</i> , 2000 , 602, 29-36	2.3	13
109	An N-Heterocyclic Carbene Based Silver Precursor for Plasma-Enhanced Spatial Atomic Layer Deposition of Silver Thin Films at Atmospheric Pressure. <i>Angewandte Chemie - International Edition</i> , 2018 , 57, 16224-16227	16.4	13
108	Tailoring iron(III) oxide nanomorphology by chemical vapor deposition: Growth and characterization. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2014 , 211, 316-322	1.6	12
107	Unearthing [3-(Dimethylamino)propyl]aluminium(III) Complexes as Novel Atomic Layer Deposition (ALD) Precursors for Al ₂ O ₃ : Synthesis, Characterization and ALD Process Development. <i>Chemistry - A European Journal</i> , 2017 , 23, 10768-10772	4.8	12
106	Growth and Characterization of Ti-Ta-O Thin Films on Si Substrates by Liquid Injection MOCVD for High-k Applications from Modified Titanium and Tantalum Precursors. <i>Chemical Vapor Deposition</i> , 2010 , 16, 157-165		12
105	An Efficient Chemical Solution Deposition Method for Epitaxial Gallium Nitride Layers Using a Single-Molecule Precursor. <i>Advanced Functional Materials</i> , 2001 , 11, 224-228	15.6	12
104	Systematic molecular engineering of Zn-ketoiminates for application as precursors in atomic layer depositions of zinc oxide. <i>Dalton Transactions</i> , 2016 , 45, 19012-19023	4.3	12
103	Atomic/molecular layer deposition of Cu-organic thin films. <i>Dalton Transactions</i> , 2018 , 47, 15791-15800	4.3	12

102	Fabrication of zinc-dicarboxylate- and zinc-pyrazolate-carboxylate-framework thin films through vapour-solid deposition. <i>Dalton Transactions</i> , 2018 , 47, 14179-14183	4.3	11
101	Influence of process parameters on the crystallinity, morphology and composition of tungsten oxide-based thin films grown by metalorganic chemical vapor deposition. <i>Thin Solid Films</i> , 2012 , 522, 11-16	2.2	11
100	Designing Stability into Thermally Reactive Plumbylenes. <i>Inorganic Chemistry</i> , 2018 , 57, 8218-8226	5.1	11
99	Up-converting ALD/MLD thin films with Yb ³⁺ , Er ³⁺ in amorphous organic framework. <i>Journal of Luminescence</i> , 2019 , 213, 310-315	3.8	10
98	Rational Development of Cobalt β -Ketoiminate Complexes: Alternative Precursors for Vapor-Phase Deposition of Spinel Cobalt Oxide Photoelectrodes. <i>Inorganic Chemistry</i> , 2018 , 57, 5133-5144	5.1	10
97	Effects of Post Annealing Treatments on the Interfacial Chemical Properties and Band Alignment of AlN/Si Structure Prepared by Atomic Layer Deposition. <i>Nanoscale Research Letters</i> , 2017 , 12, 102	5	10
96	Surface Decoration of γ -Fe ₂ O ₃ Nanorods by CuO Via a Two-Step CVD/Sputtering Approach**. <i>Chemical Vapor Deposition</i> , 2014 , 20, 313-319		10
95	Liquid injection MOCVD of TiO ₂ and SrTiO ₃ thin films from [Ti(OPri) ₂ (tbaaac) ₂]: Film properties and compatibility with [Sr(thd) ₂]. <i>Surface and Coatings Technology</i> , 2007 , 201, 9135-9140	4.4	10
94	MOCVD of aluminium oxide films using aluminium β -diketonates as precursors. <i>European Physical Journal Special Topics</i> , 2002 , 12, 139-146		10
93	Low-Temperature Structure of Two Copper-Based Precursors for MOCVD: Aquabis(tert-butyl acetoacetato)copper(II) and Bis(dipivaloylmethanido)copper(II). <i>Acta Crystallographica Section C: Crystal Structure Communications</i> , 1996 , 52, 891-894		10
92	Spectroscopic investigation of wheat grains (<i>Triticum aestivum</i>) infected by wheat seed gall nematodes (<i>Anguina tritici</i>). <i>Biocatalysis and Agricultural Biotechnology</i> , 2017 , 9, 58-66	4.2	9
91	Rare-earth substituted HfO ₂ thin films grown by metalorganic chemical vapor deposition. <i>Thin Solid Films</i> , 2012 , 520, 4512-4517	2.2	9
90	Growth of epitaxial sodium-bismuth-titanate films by metal-organic chemical vapor phase deposition. <i>Thin Solid Films</i> , 2011 , 520, 239-244	2.2	9
89	Innovative M(Hfa) ₂ TMEDA (M=Cu, Co) Precursors for the CVD of Copper-Cobalt Oxides: an Integrated Theoretical and Experimental Approach. <i>ECS Transactions</i> , 2009 , 25, 549-556	1	9
88	Thermal chemical vapour deposition of copper films from copper ethylacetoacetate: microstructure and electrical resistivity. <i>Journal of Materials Science Letters</i> , 1998 , 17, 367-369		9
87	Comparative Study of Photocatalytic Dynamics in CVD-deposited CuWO ₄ , CuO, and WO ₃ Thin Films for Photoelectrocatalysis. <i>Zeitschrift Fur Physikalische Chemie</i> , 2020 , 234, 699-717	3.1	9
86	Study on Structural and Thermal Characteristics of Heteroleptic Yttrium Complexes as Potential Precursors for Vapor Phase Deposition. <i>European Journal of Inorganic Chemistry</i> , 2020 , 2020, 3587-3596	2.3	9
85	PEALD of HfO Thin Films: Precursor Tuning and a New Near-Ambient-Pressure XPS Approach to in Situ Examination of Thin-Film Surfaces Exposed to Reactive Gases. <i>ACS Applied Materials & Interfaces</i> , 2019 , 11, 28407-28422	9.5	8

84	Engineered Tungsten Oxy-Nitride Thin Film Materials for Photocatalytical Water Splitting Fabricated by MOCVD. <i>ECS Transactions</i> , 2010 , 28, 159-165	1	8
83	Morphology controlled growth of arrays of GaN nanopillars and randomly distributed GaN nanowires on sapphire using (N ₃) ₂ Ga[(CH ₂) ₃ NMe ₂] as a single molecule precursor. <i>Chemical Communications</i> , 2002 , 998-9	5.8	8
82	Epitaxy, Composites and Colloids of Gallium Nitride Achieved by Transformation of Single Source Precursor. <i>Physica Status Solidi A</i> , 2000 , 177, 27-35		8
81	Thermal Analysis of Metalorganic Complexes of Copper for Evaluation as CVD Precursors. <i>Magyar Árvad Kélemlyek</i> , 1999 , 55, 259-270	0	8
80	A cobalt(ii)heteroarylalkenolate precursor for homogeneous CoO coatings by atomic layer deposition. <i>Dalton Transactions</i> , 2017 , 46, 12996-13001	4.3	8
79	A new metalorganic chemical vapor deposition process for MoS with a 1,4-diazabutadienyl stabilized molybdenum precursor and elemental sulfur. <i>Dalton Transactions</i> , 2020 , 49, 13462-13474	4.3	8
78	Influence of PE-CVD and PE-ALD on defect formation in permeation barrier films on PET and correlation to atomic oxygen fluence. <i>Journal Physics D: Applied Physics</i> , 2017 , 50, 235201	3	7
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